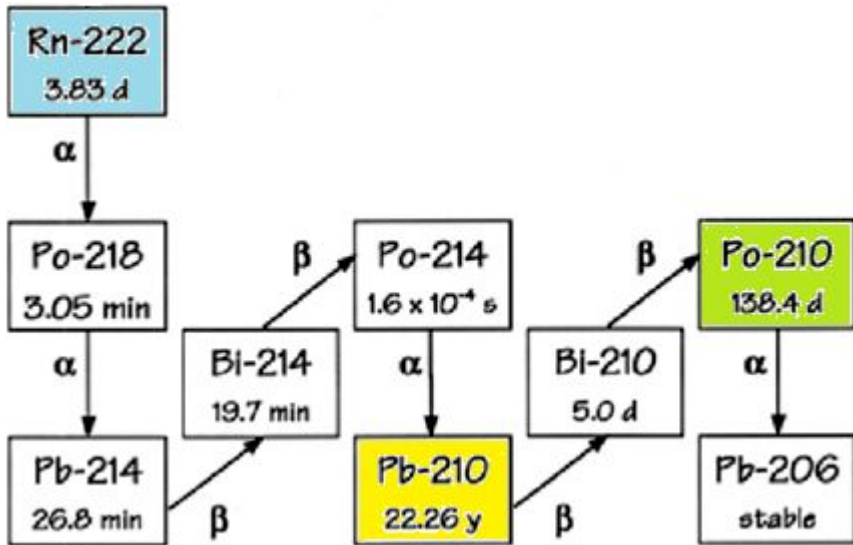


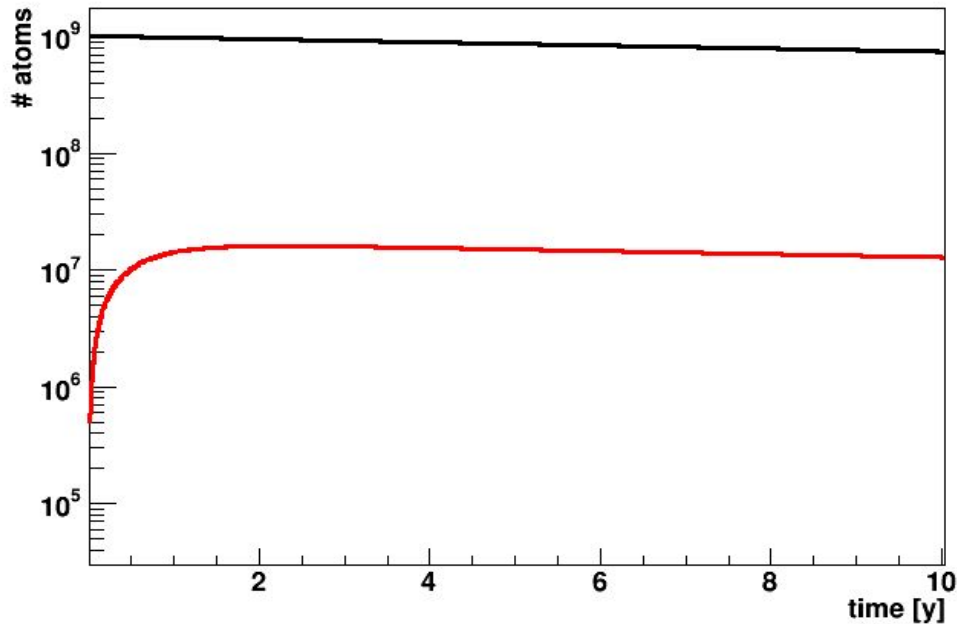
Surface contamination

DS-Mat

Pb-210 and Po-210 contamination

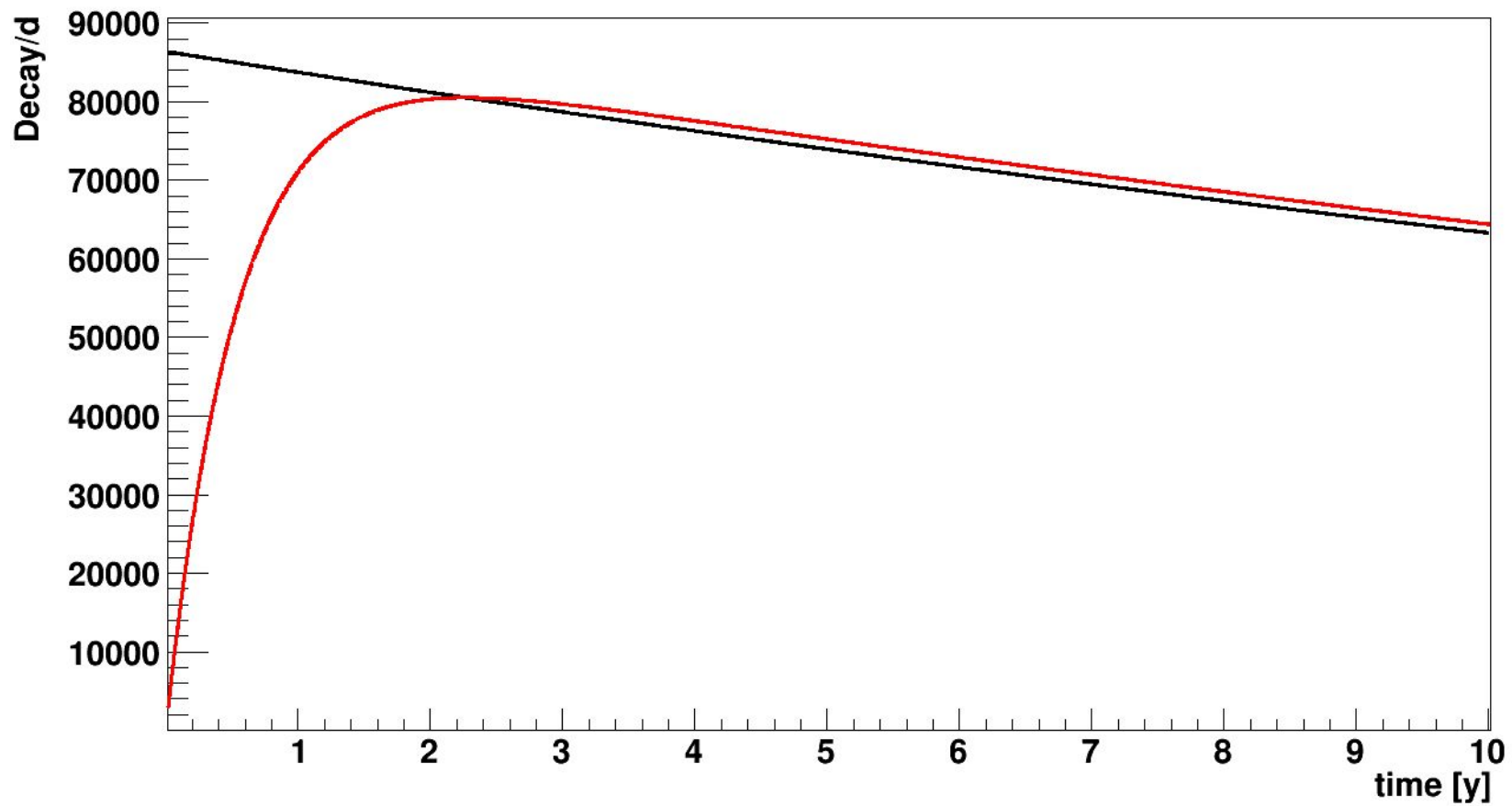


Pb-210 main source of Po-210

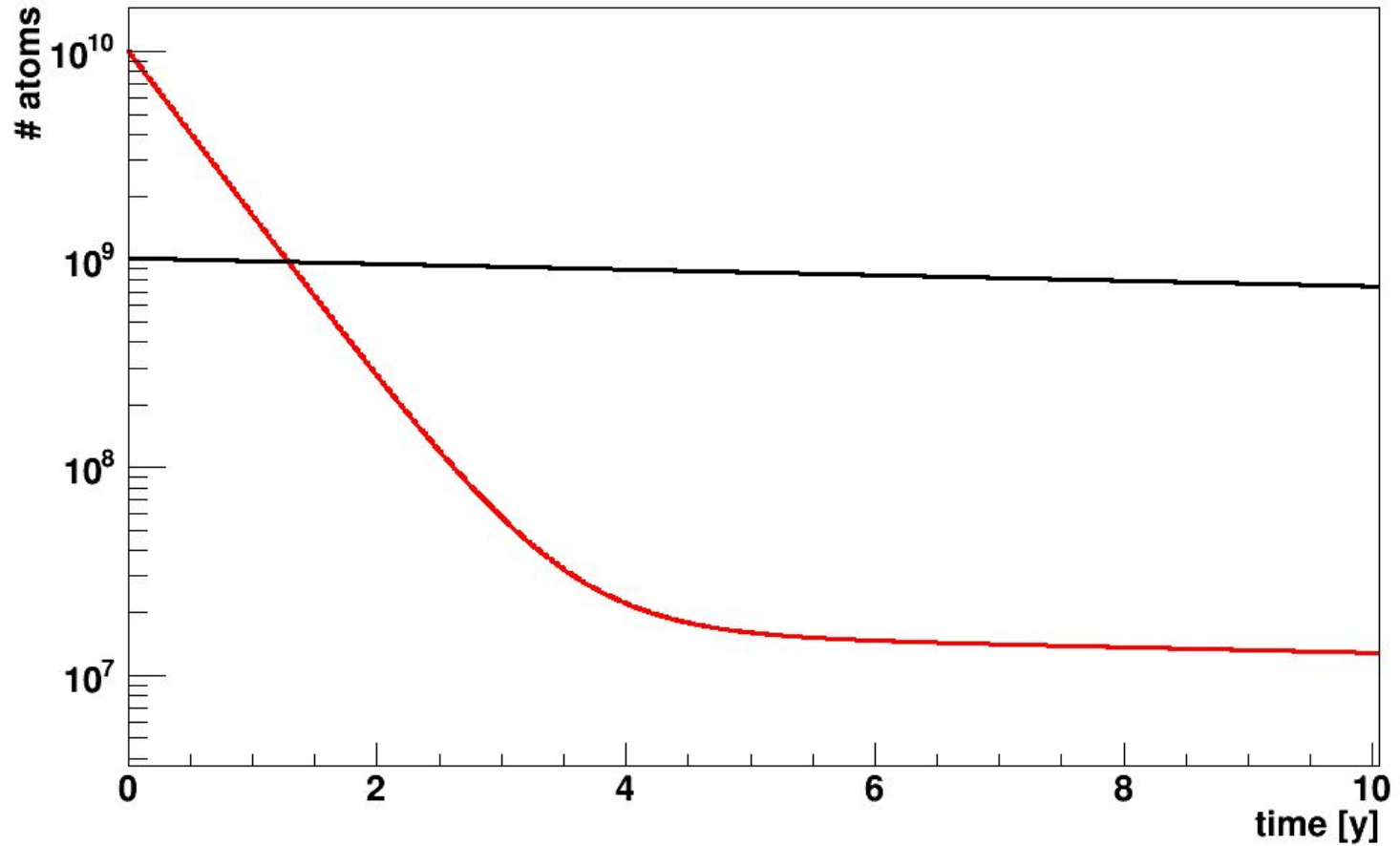


1 Bq Pb-210 -> 1.015253e+09 atoms

1 Bq Po-210 -> 1.725140e+07 atoms



No-equilibrium ($N_{\text{Po210}}^0 = 10 \times N_{\text{Pb210}}^0$)



High-activity case

| Isotope | Activity reduction factors after etching/electropolishing | | | |
|-------------------|---|-----------------|----------|---------|
| | Copper | Stainless steel | NPGe | HPGe |
| ^{210}Pb | 50 / 300 | 100 / 400 | 100 / – | 700 / – |
| ^{210}Bi | 50 / 300 | 100 / 800 | 400 / – | 800 / – |
| ^{210}Po | 1 / 400 | 20 / 700 | 1000 / – | 100 / – |

Copper

- etching: 5 min in (1% H_2SO_4 + 3% H_2O_2) and 5 min in 1% citric acid
- electro-polishing: 85 % H_3PO_4 + 5 % 1-butanol ($\text{C}_4\text{H}_{10}\text{O}$)

Stainless steel:

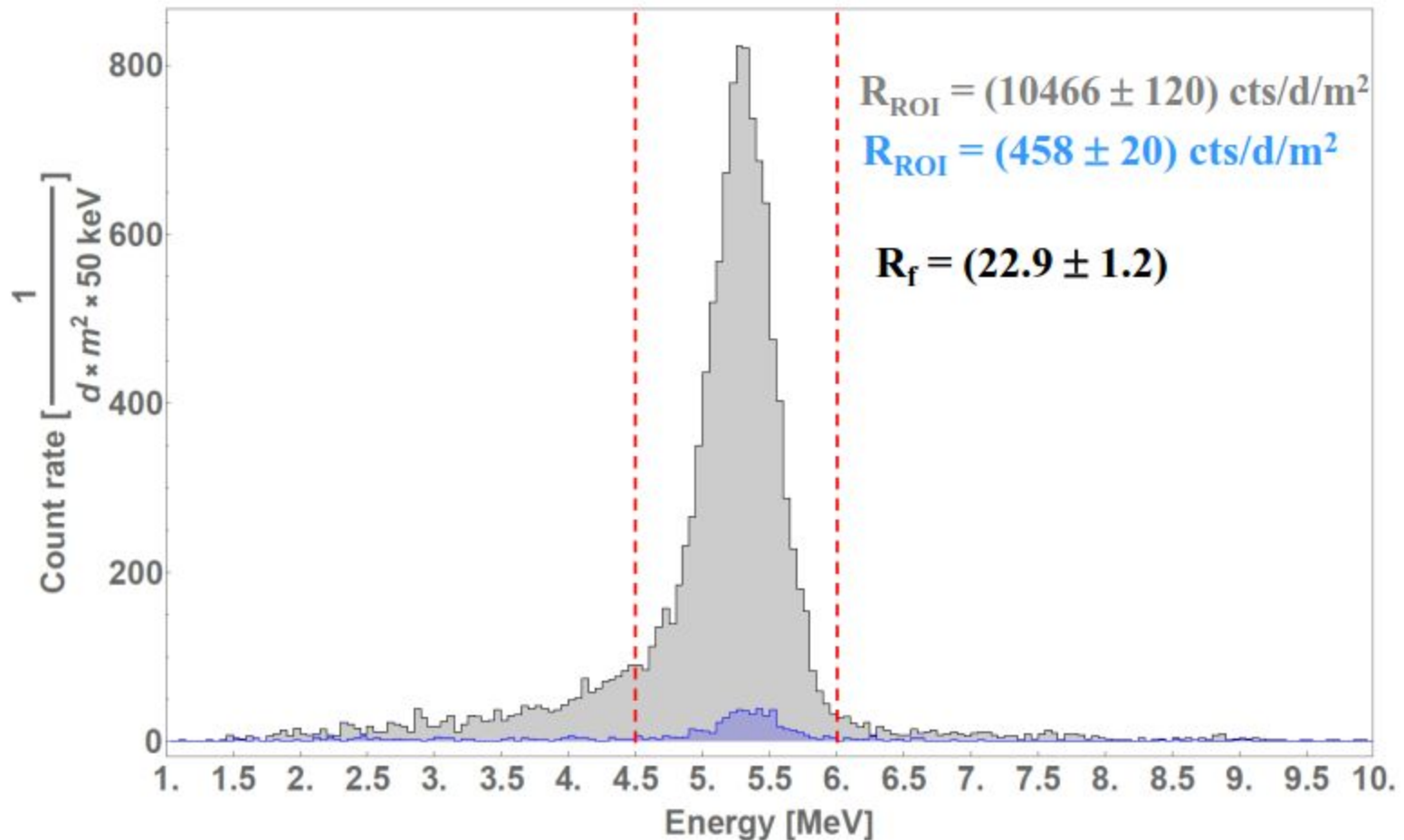
- etching: (20 % HNO_3 + 1.7 % HF) and 15 % HNO_3
- electro-polishing: 40 % H_3PO_4 + 40 % H_2SO_4 + 3 % CrO_3

Germanium:

- etching: CP4 solution (45.45 ml HNO_3 + 27.27 ml HF + 27.27 ml CH_3COOH + 0.5 ml Br for 100 ml solvent) done by Canberra-France in Lingolsheim in cooperation with MPP Munich

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„Dynamic” etching



- Etching procedure: 5 x 1 min wash with a mixture of 1% H_2SO_4 + 3% H_2O_2
- Passivation with 1% citric acid at the end
- Washing in high-purity deionized water (18 $\text{M}\Omega \times \text{cm}$)

Impact of the surface ^{210}Po contamination on the bkg budget

Assumptions:

- Rn plate-out rate (only): **250 atoms/day/cm²** (based on SNOLAB measurement for 153 Bq/m³). **INDEPENDENTLY of material.**
- Considered the plate-out rate proportional to Rn activity. No other effects.
- Surfaces (m²) :

surface barrel = 41.244

surface caps = 10.4764

surfAcryTPC = 124.394

surfAcryVeto = 880

surfSS = 28

surfCuElec = 209.528

surfElec = 209.528

surfCuVeto = 248.787

Evolution of activity in time taken into account (10 y is a good fraction of 22.2 y)

Impact of the surface ^{210}Po contamination on the bkg budget

Cases:

- Exposure
 - 1 day
 - 6 months
- Environment activity
 - 153 Bq/m^3
 - 0.1 Bq/m^3

Both are considered to have a linear effect.

Impact of the surface ^{210}Po contamination on the bkg budget

Case 1 day + clean:

| nSource | Before CUTS | | | After CUTS | | |
|--------------|-------------|---------|---------|------------|----------|----------------|
| | Self pr. | Argon | Sum | Self pr. | Argon | Sum |
| AcryTPC | 3.14E-3 | 5.76E-3 | 8.91E-3 | 2.26E-8 | 4.15E-8 | 6.41E-8 |
| AcryVeto | 2.22E-2 | 4.08E-2 | 6.30E-2 | 1.29E-8 | 2.37E-8 | 3.66E-8 |
| SS_TPC | 6.49E-4 | 1.30E-3 | 1.95E-3 | 4.35E-10 | 8.69E-10 | 1.30E-9 |
| Cu_Elec | 1.41E-3 | 9.71E-3 | 1.11E-2 | 1.02E-8 | 6.99E-8 | 8.01E-8 |
| Cu_FC | 1.68E-3 | 1.15E-2 | 1.32E-2 | 9.73E-10 | 6.69E-9 | 7.66E-9 |
| Elec | 6.62E-3 | 9.71E-3 | 1.63E-2 | 4.77E-8 | 6.99E-8 | 1.18E-7 |
| TOTAL | 3.57E-2 | 7.88E-2 | 1.15E-1 | 9.48E-8 | 2.13E-7 | 3.07E-7 |

Impact of the surface ^{210}Po contamination on the bkg budget

Case 6 months + clean:

| nSource | Before CUTS | | | After CUTS | | |
|--------------|-------------|---------|---------|------------|---------|----------------|
| | Self pr. | Argon | Sum | Self pr. | Argon | Sum |
| AcryTPC | 5.66E-1 | 1.04E+0 | 1.60E+0 | 4.07E-6 | 7.47E-6 | 1.15E-5 |
| AcryVeto | 4.00E+0 | 7.34E+0 | 1.13E+1 | 2.32E-6 | 4.26E-6 | 6.58E-6 |
| SS_TPC | 1.17E-1 | 2.34E-1 | 3.50E-1 | 7.82E-8 | 1.56E-7 | 2.35E-7 |
| Cu_Elec | 2.54E-1 | 1.75E+0 | 2.00E+0 | 1.83E-6 | 1.26E-5 | 1.44E-5 |
| Cu_FC | 3.02E-1 | 2.08E+0 | 2.38E+0 | 1.75E-7 | 1.20E-6 | 1.38E-6 |
| Elec | 1.19E+0 | 1.75E+0 | 2.94E+0 | 8.58E-6 | 1.26E-5 | 2.12E-5 |
| TOTAL | 6.43E+0 | 1.42E+1 | 2.06E+1 | 1.71E-5 | 3.83E-5 | 5.53E-5 |

Impact of the surface ^{210}Po contamination on the bkg budget

Case 1 day + dirty:

| nSource | Before CUTS | | | After CUTS | | |
|--------------|-------------|---------|---------|------------|---------|----------------|
| | Self pr. | Argon | Sum | Self pr. | Argon | Sum |
| AcryTPC | 4.81E+0 | 8.82E+0 | 1.36E+1 | 3.46E-5 | 6.35E-5 | 9.81E-5 |
| AcryVeto | 3.40E+1 | 6.24E+1 | 9.64E+1 | 1.97E-5 | 3.62E-5 | 5.59E-5 |
| SS_TPC | 9.93E-1 | 1.99E+0 | 2.98E+0 | 6.65E-7 | 1.33E-6 | 2.00E-6 |
| Cu_Elec | 2.16E+0 | 1.49E+1 | 1.70E+1 | 1.56E-5 | 1.07E-4 | 1.23E-4 |
| Cu_FC | 2.57E+0 | 1.76E+1 | 2.02E+1 | 1.49E-6 | 1.02E-5 | 1.17E-5 |
| Elec | 1.01E+1 | 1.49E+1 | 2.50E+1 | 7.29E-5 | 1.07E-4 | 1.80E-4 |
| TOTAL | 5.47E+1 | 1.21E+2 | 1.75E+2 | 1.45E-4 | 3.25E-4 | 4.70E-4 |

Impact of the surface ^{210}Po contamination on the bkg budget

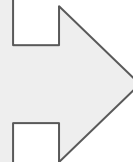
Case 6 months + dirty:

| nSource | Before CUTS | | | After CUTS | | |
|--------------|-------------|---------|---------|------------|---------|----------------|
| | Self pr. | Argon | Sum | Self pr. | Argon | Sum |
| AcryTPC | 8.66E+2 | 1.59E+3 | 2.45E+3 | 6.23E-3 | 1.14E-2 | 1.77E-2 |
| AcryVeto | 6.13E+3 | 1.12E+4 | 1.74E+4 | 3.55E-3 | 6.51E-3 | 1.01E-2 |
| SS_TPC | 1.79E+2 | 3.57E+2 | 5.36E+2 | 1.20E-4 | 2.39E-4 | 3.59E-4 |
| Cu_Elec | 3.89E+2 | 2.67E+3 | 3.06E+3 | 2.80E-3 | 1.93E-2 | 2.21E-2 |
| Cu_FC | 4.62E+2 | 3.17E+3 | 3.64E+3 | 2.68E-4 | 1.84E-3 | 2.11E-3 |
| Elec | 1.82E+3 | 2.67E+3 | 4.50E+3 | 1.31E-2 | 1.93E-2 | 3.24E-2 |
| TOTAL | 9.84E+3 | 2.17E+4 | 3.15E+4 | 2.61E-2 | 5.85E-2 | 8.46E-2 |

Cleaning protocols (manipulation and packaging)

- Copper (this should be OK):
 - a. Tumbling
 - b. electropolishing
 - c. Specific chemical etching (SUBU)
- Stainless Steel (similar protocol of Copper)
 - a. Tumbling
 - b. electropolishing
 - c. chemical etching
- Acrylic (for small or fragile components)
 - a. atmospheric plasma treatments

- Reflectors?
- Electronics (cable? components?)
- more?



Parylene coating ???

SS

- Electropolishing necessary? (bars? Entire Structure?)
- Dimensions and Welding details needed
- Welding Rn emanation: possible measurements

Electronics

- What is the possible impact?
- Total surface?
- a,n yield in worst scenario (entire ^{210}Po contamination on the surface)

Conclusion:

Rn plate-out is a relevant source of n-bkg. It needs to be mitigated:

- We need to avoid exposure to Rn in all steps
- Materials have to be stored in Rn-free atmosphere
- We need to foresee surface cleaning protocols